

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Ibrahim Abdulhalim, et al.
Title: Periodic Patterns And Technique To Control Misalignment Between Two Layers
Application No.: 09/833,084 Filing Date: April 10, 2001
Examiner: Zandra V. Smith Group Art Unit: 1775
Docket No.: TNCR.196US0 Conf. No.: 8866

Certificate of Mailing Under 37 CFR 1.8

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Traeynn Knox

Commissioner for Patents
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.

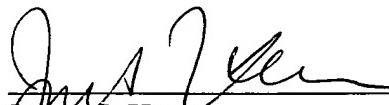
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Attorney Docket No.:
TNCR.196US0

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09/833,084

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Respectfully submitted,



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3/1/04

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U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Atty. Docket No. TNCR.196US0	Application No. 09/833,084
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<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>			